Amendments to the Specification

Please replace the paragraph beginning with line 16, page 2 and ending with line 5, page 3 with the following paragraph:

With reference to Fig. 2A-2~~G~~F, a conventional manufacturing ~~processes~~ process of an organic electroluminescent display ~~are~~ is shown. A plurality of first display electrodes 210 of stripe shapes arranged in parallel are formed on a glass substrate 200 by a sputtering process, as shown in Fig. 2A. A layer of insulating ~~materials~~ material 220 ~~are~~ is spin-coated on the substrate 200 with the first display electrodes 210 disposed thereon. Then, shadow masks are disposed on the insulating ~~materials~~ material 220, and after a photolithography process, openings 225 having a direction perpendicular to that of the first display electrodes 210 are formed, ~~and~~ thereby exposing the first display electrodes 210 partially, as shown in the top view of Fig. 2B and the sectional view of Fig. 2C. Next, as shown in Fig. 2D, a layer of photoresistant ~~materials~~ material 230 ~~are~~ is formed on the insulating ~~materials 200~~ material 220 having openings 225. With reference to Fig. 2E, photo masks 235 are formed on the photoresistant ~~materials~~ material 230 and are illuminated by parallel light beams I. Due to the mask effect of the photo masks 235, only the portions of the photoresistant ~~materials~~ material 230, i.e. the mesh areas, are illuminated by the light beams I. Subsequently, a developing process is conducted ~~to~~ on the photoresistant ~~materials~~ material 230 so as to form a shape of cathode ramparts shown in Fig. 2F. Finally, an organic electroluminescent material is formed on the exposed first display electrodes and then a plurality of second display electrodes are formed on the organic electroluminescent ~~materials~~ material such that an organic electroluminescent display is completed.

Please replace the paragraph beginning with line 23, page 4 and ending with line 10, page 5 with the following paragraph:

An alternative method for manufacturing an organic electroluminescent display according to the present invention comprises the steps of providing a substantially transparent substrate; forming a plurality of first display electrodes arranged in parallel on said substrate; forming a non-photosensitive insulating layer on said substrate with the first display electrodes disposed thereon; ~~pre-baking and baking~~ imidizing said non-photosensitive insulating layer by baking; forming a photosensitive insulating layer on said non-photosensitive insulating layer, and pre-baking ~~thereto~~ said photosensitive insulating layer; proceeding a photolithography process ~~to~~ on said photosensitive insulating layer so as to define a shape perpendicular to that of the first display electrodes, and proceeding a post-exposure baking ~~thereto~~ thereon; disposing an aggregate composed of said substrate with said first display electrodes, said non-photosensitive insulating layer and said photosensitive insulating layer disposed thereon into developers, whereby said photosensitive insulating layer is partially removed through development and said non-photosensitive insulating layer is partially removed by etching, and thereby said first display electrodes are exposed partially; proceeding to a ~~final cure~~ curing process ~~to~~ on said aggregate; forming an organic electroluminescent material on the exposed first display electrodes; and forming a plurality of second display electrodes on the organic electroluminescent material.

Please replace the paragraph beginning with line 15, page 9 and ending with line 23, page 9 with the following paragraph:

With reference to Fig. 3B, a blanket of non-photosensitive insulating ~~materials~~ material 320, preferably made of thermal type polyimide, is spin-coated on the substrate 300 with the first

display electrodes 310 disposed thereon about 0.5-2μm thickness for covering both the first display electrodes 310 and the substrate 300 exposed. Then, a ~~pre-baking~~ first baking process is conducted ~~to~~ on the non-photosensitive insulating ~~materials~~ material 320 to remove the presence of solvent ~~existed~~ therein, and a ~~-baking~~ second baking process is subsequently conducted ~~thereto~~ at a temperature between 120-180 Celsius degrees for 20 minutes to 1 hour to imidize the non-photosensitive insulating ~~materials~~ material 320, and thereby create ~~a~~ partial cross-linking thereof ~~effect occurs thereto~~.

Please replace the paragraph beginning with line 25, page 9 and ending with line 6, page 10 with the following paragraph:

With reference to Fig. 3C, a blanket of photosensitive insulating ~~materials~~ material 330 is spin-coated on the non-photosensitive insulating ~~materials~~ material 320 with a thickness of about 3-5μm ~~thickness~~ as negative photoresists. Then, a pre-baking process is conducted to the photosensitive insulating ~~materials~~ material 330 to remove the solvent existed therein. Subsequently, photo masks 335 are disposed on the photosensitive insulating ~~materials~~ material 330, and after a photolithography process, a shape perpendicular to the first display electrodes 310 ~~are~~ is defined in the photosensitive insulating ~~materials~~ material 330, wherein the exposure is proceeded at 30-80 mJ/cm^2. As shown in Fig. 3C, the portions of the photosensitive insulating ~~materials~~ material 330 illuminated during exposure process is represented as mesh areas. Then, a post-exposure baking process is conducted at a temperature between 90-150 Celsius degrees for 30-120 seconds to remove the solvent in the photosensitive insulating ~~materials~~ material 330.

Please replace the paragraph beginning with line 8, page 10 and ending with line 23, page 10 with the following paragraph:

The whole aggregate is then disposed into or sprayed with developers, such as TMAH 2.38%, at room temperature for 50-100 seconds, such that the photosensitive insulating ~~materials~~ material 330 is partially removed through developing effect. After that, the non-photosensitive insulating ~~materials~~ material 320 ~~are~~ is partially removed through wet-etching by the developers due to the partial cross-linking effect imparted during ~~baking process~~ baking of the non-photosensitive insulating material 320. Since the adhesion between the non-photosensitive insulating ~~materials~~ material 320 and the photosensitive insulating ~~materials~~ material 330 is weaker, the photosensitive insulating ~~materials~~ material 330 is developed to be of a reversed trapezoid shape and the non-photosensitive insulating ~~materials~~ material 320 is etched to be of a trapezoid shape as shown in Fig. 3D. It should be noted that the long base ~~side~~ of the reversed trapezoid shape of the photosensitive insulating ~~materials~~ material 330 is shorter than that of the trapezoid shape of the non-photosensitive insulating ~~materials~~ material 320, such that short circuit between the second display electrodes, which will be formed in the subsequent process, and the first display electrodes is avoided. Then, a ~~final~~ curing process is conducted at a temperature between 200-350 Celsius degrees for 30 minutes to 2 hours, and thereby completing the formation of the cathode ramparts.

Please replace the paragraph beginning with line 25, page 10 and ending with line 3, page 11 with the following paragraph:

Next, organic electroluminescent ~~materials~~ material 340 ~~are~~ is formed on the exposed first display electrodes 310, as shown in Fig. 3E. While producing single-color organic

electroluminescent displays, an organic electroluminescent layer is coated through evaporation on the exposed first display electrodes 310. While producing full-color organic electroluminescent displays, RGB organic electroluminescent layers are formed in turn on the exposed first display electrodes 310 by using shadow masks. Subsequently, metal conductive materials 350, such as Al, Mg-Al alloy or other suitable metal materials, are formed on the organic electroluminescent materials 340 as cathode electrodes of the organic electroluminescent displays.

Please replace the paragraph beginning with line 5, page 11 and ending with line 15, page 11 with the following paragraph:

Fig. 4A-4D are the schematic drawings illustrating the manufacturing processes of an organic electroluminescent display according to another embodiment of the present invention. In this case, a plurality of first display electrodes 410 made of, for example, ITO or In_2O_3-ZnO as anode electrodes of the organic electroluminescent display of stripe shape arranged in parallel are formed on a substrate 400. Then, first photosensitive insulating ~~materials~~ material 420 and second photosensitive insulating ~~materials~~ material 430 are in turn formed on the substrate 400 with first display electrodes 410 disposed thereon as negative photoresists, for example, as shown in Fig. 4B. It should be noted that the photosensitivity of the first photosensitive insulating ~~materials~~ material 420 is greater than that of the second photosensitive insulating ~~materials~~ material 430.

Please replace the paragraph beginning with line 17, page 11 and ending with line 2, page 12 with the following paragraph:

Next, photo masks 435 are disposed on the second photosensitive insulating ~~materials~~ material 430 and a photolithography process is conducted to the second photosensitive insulating ~~materials~~ material 430 and ~~thus to~~ the first photosensitive insulating ~~materials~~ material 420 such that a shape perpendicular to the first display electrodes is defined therein. With reference to Fig. 4C, parallel light beams I incident to the second photosensitive insulating ~~materials~~ material 430 and ~~thus to~~ the first photosensitive insulating ~~materials~~ material 420 are irradiated on the photo masks 435. Due to the masking effect of the photo masks 435, only the portions of the second photosensitive insulating ~~materials~~ material 430 and ~~of the~~ first photosensitive insulating ~~materials~~ material 420 marked by mesh areas are illuminated by the light beams I. Subsequently, a developing process is conducted ~~to~~ on the second photosensitive insulating ~~materials~~ material 430 and the first photosensitive insulating ~~materials~~ material 420 and thereby forming cathode ramparts of shapes shown in Fig. 4D. Finally, organic electroluminescent ~~materials~~ material 440 ~~are~~ is formed on the exposed first display electrodes 410, and metal conductive materials 450 are formed on the organic electroluminescent ~~materials~~ material 440 as cathode electrodes of the organic electroluminescent displays.